

P7: Chemical and Biological Operations

Based on:

031-COM-1004-Protect Yourself from Chemical and Biological (CB) Contamination Using Your Assigned Protective Mask

031-COM-1006-Decontaminate Your Skin

031-COM-1011-Decontaminate Individual Equipment

Task: Assume Mission Oriented Protective Posture (MOPP) level three. Decontaminate your skin and equipment, assuming MOPP level four.

Condition: You are a member of a platoon within a secure Forward Operating Base (FOB). You are in MOPP level two when you suspect a chemical/biological attack.

Standard: Don, clear, and seal the mask within nine seconds and perform all remaining tasks to standard, in sequence. Decontaminate your skin using the RSDL, in sequence within a two-minute period. Decontaminate your individual equipment using a M334 or M295 in sequence within 5 minutes.

Station Requirements: Candidate's own functional, properly maintained mask with optional mask hood. Properly fitted Joint-service lightweight integrated suit technology (JSLIST) coat, trousers, over-boots, and gloves for the Candidate to wear. Training decontamination lotion and wipes/mitts or simulated materials; standard is written for wipes. Poncho or overhead cover.

Assume MOPP Level Three:

1. Don mask assembly.
 - a. Stop Breathing and close eyes. **Nine second time standard starts.**
 - b. Remove helmet, put helmet between legs above knees or hold rifle between legs and place helmet on the muzzle. *Note: If helmet falls continue to mask.*
 - c. Take off glasses and place in helmet, if applicable.
 - d. Open the mask carrier with non-firing hand.
 - e. Grasp the mask assembly with firing hand and remove it from the carrier.
 - f. Place chin in the chin pocket and press the face piece tight against face.
 - g. Hold mask assembly tightly against face.
 - h. Grasp the harness tab, pull the harness over and down the head as far as possible. *Note: Ensure the head harness is centered on the crown of the head and the temple straps are approximately parallel to the ground.*
 - i. Grasp the loose end of the cheek straps, one at a time, and pull until strap feels tight. *Note: Both straps should be approximately equal length when complete. The temple and forehead straps have already been adjusted during fitting; do not tighten.*
2. Clear mask assembly.
 - a. Seal the outlet disk valve by placing one hand over the outlet valve cover assembly.
 - b. Blow out hard to ensure that any contaminated air is forced out around the edges of the face piece.
3. Seal mask assembly.
 - a. Cover both filter inlet ports with the palms of your hands and breathe in.
 - b. Ensure mask assembly collapse against the face.
 - c. Resume breathing. **Nine second time standard stops.**
4. Give the alarm.
 - a. Shout, "Gas, Gas, Gas."
 - b. Give the appropriate hand-and-arm signal per unit SOP.
5. Close mask carrier.

Assume MOPP Level Four: Two-minute time standard begins.

1. Seek overhead cover or use a poncho for protection against further contamination; put helmet down.
2. Decontaminate your hands, face, and the inside of your mask.
 - a. Remove one RSDL packet from your carrying pouch.

Safety: Avoid contact with eyes and wounds. If contact with eyes or wounds occurs, rinse with water as soon as possible.

- b. Tear it open quickly at any notch.
- c. Remove the applicator pad from the packet and save the packet as the remaining lotion can be added to the applicator pad, if required.
- d. Thoroughly scrub the exposed skin of your hand, palm, and fingers with the applicator pad.

Note: The applicator pad can be used from either side and may be gripped in any manner allowing the applicator pad to be applied to the skin.

- e. Switch the applicator pad to the other hand and repeat the procedure.
- f. Stop breathing, close eyes, grasp mask beneath chin and pull mask away from chin enough to allow one hand between the mask and your face. Hold the mask in this position during steps (g.) through (m.).
- g. Thoroughly scrub the exposed skin of your face with lotion from the applicator pad.
- h. Thoroughly scrub across your forehead.
- i. Beginning at one side, scrub up and down across your cheeks, nose, chin, and closed mouth. Avoid ingesting.
- j. Scrub under the chin from the ear along the jawbone to the other ear to coat your skin with lotion.
- k. Turn your hand over and scrub the inside surfaces of the mask that may touch your skin. Be sure to include the drinking tube.

Note: Do not apply lotion to the lens of the protective mask. The RSDL may cause loss of transparency.

- l. Keep the applicator.
- m. Seal your mask immediately, clear it, and check it as per steps 2-3 in 'Assume MOPP Level 3' above.
- n. Use the applicator and any remaining lotion in the packet. Without breaking the mask seal, scrub the applicator pad across the forehead, exposed scalp, the skin of the neck, ears, and throat.
- o. Secure the hood.
- p. Thoroughly scrub your hands with lotion again as in the steps (2d.) and (2e.) above.
- q. Assume MOPP Level 4 by putting on protective gloves; fasten Velcro. **Two-minute time standard ends.**

ends.

3. Decontaminate your equipment (M295 or M334). Five-minute time standard begins.

- a. Open the M334 at either end where the Kit is notched.
- b. Remove one M334 packet from the kit.
- c. Open an M334 packet at a notch on the packet.
- d. Remove the individual wipe from the packet and unfold completely.
- e. Decontaminate all contaminated individual equipment by wiping the surface using sweeping motions away from the body. Take care not to spread contamination to any area that has been visually determined clean. *Note: M334 individual wipe may leave behind a film on decontaminated surfaces. This film may alter how certain surfaces (i.e., optics, reflective surfaces) process light. Refer to the decontaminated equipment's TM for cleaning procedures, as some surfaces may require specific procedures to avoid damaging the surface.*

In the absence of cleaning procedures, a lens cloth has been found to be an effective means of removing any film left behind by the M334 individual wipe.

Note: The wipe may be folded/refolded as necessary to maximize use of the clean areas of the wipe, to obtain the proper grip, and to ensure even contact pressure. When wiping, pay special attention to areas that are hard to reach, such as cracks, crevices, and absorbent materials. To avoid premature evaporation of the solvent, do not open a new M334 packet until needed.

- f. Dispose of contaminated waste material IAW unit SOP and local and federal regulations.